

Title (en)

Uniform gas distribution in large area plasma treatment device

Title (de)

Gleichmässige Gasverteilung in einer grossflächige Plasma-Behandlungs-Vorrichtung

Title (fr)

Répartition uniforme de gaz dans un appareil de traitement par plasma à grande surface

Publication

EP 1089319 B1 20090107 (EN)

Application

EP 99402374 A 19990929

Priority

EP 99402374 A 19990929

Abstract (en)

[origin: EP1089319A1] The apparatus generates a time-varying magnetic field through a field admission window (22) of a plasma processing chamber (20) to create or sustain a plasma within the chamber by inductive coupling. It comprises: a magnetic core (38) presenting a unipolar pole face structure (38a) an inductor means (40) associated with the magnetic core, for generating a time-varying magnetic field throughout the unipolar pole face structure, means (42,44,48,51) for injecting gas into said chamber and through said magnetic core. <IMAGE>

IPC 8 full level

H01J 37/32 (2006.01); **H05H 1/46** (2006.01); **B01J 19/08** (2006.01); **C23C 16/505** (2006.01)

CPC (source: EP KR US)

C23C 16/4401 (2013.01 - KR); **H01J 37/321** (2013.01 - EP KR US); **H01J 37/3244** (2013.01 - EP KR US); **H01J 37/32495** (2013.01 - KR); **H01J 37/32816** (2013.01 - KR)

Cited by

KR100760830B1; EP1662546A1; US8021515B2; WO2006056573A1

Designated contracting state (EPC)

AT BE CH CY DE DK ES FI FR GB GR IE IT LI LU MC NL PT SE

DOCDB simple family (publication)

EP 1089319 A1 20010404; **EP 1089319 B1 20090107**; AT E420453 T1 20090115; CA 2386078 A1 20010405; CA 2386078 C 20100330; DE 69940260 D1 20090226; DK 1089319 T3 20090406; ES 2320501 T3 20090522; IL 148912 A0 20020912; JP 2003510780 A 20030318; KR 100797206 B1 20080122; KR 20020048415 A 20020622; NO 20021492 D0 20020326; NO 20021492 L 20020527; NO 327017 B1 20090406; US 6682630 B1 20040127; WO 0124220 A2 20010405; WO 0124220 A3 20010621

DOCDB simple family (application)

EP 99402374 A 19990929; AT 99402374 T 19990929; CA 2386078 A 20000918; DE 69940260 T 19990929; DK 99402374 T 19990929; EP 0009996 W 20000918; ES 99402374 T 19990929; IL 14891200 A 20000918; JP 2001527314 A 20000918; KR 20027003754 A 20020321; NO 20021492 A 20020326; US 8851202 A 20020329